AgnÃ¨s GranÃ-er

List of Publications by Year
in descending order

105 papers	2,500 citations	186265 28 h-index	243625 44 g-index
105 all docs	105 docs citations	105 times ranked	2023 citing authors

#	Article	IF	Citations
1	A comparative study of oxygen/organosilicon plasmas and thin SiOxCyHz films deposited in a helicon reactor. Thin Solid Films, 2000, 359, 188-196.	1.8	124
2	Diagnostics in helicon plasmas for deposition. Plasma Sources Science and Technology, 1997, 6, 147-156.	3.1	92
3	Microwave discharge in H2: influence of H-atom density on the power balance. Journal Physics D: Applied Physics, 1994, 27, 1412-1422.	2.8	83
4	Microwave discharges produced by surface waves in argon gas. Journal Physics D: Applied Physics, 1987, 20, 197-203.	2.8	82
5	Validity of actinometry to monitor oxygen atom concentration in microwave discharges created by surface wave in O2â€N2mixtures. Journal of Applied Physics, 1994, 75, 104-114.	2.5	80
6	Wave propagation and diagnostics in argon surface-wave discharges up to 100 Torr. Journal Physics D: Applied Physics, 1987, 20, 204-209.	2.8	67
7	Optical emission spectra of TEOS and HMDSO derived plasmas used for thin film deposition. Plasma Sources Science and Technology, 2003, 12, 89-96.	3.1	66
8	Inorganic to organic crossover in thin films deposited from O2/TEOS plasmas. Journal of Non-Crystalline Solids, 2000, 272, 163-173.	3.1	64
9	XPS study of the surface composition modification of nc-TiC/C nanocomposite films under in situ argon ion bombardment. Thin Solid Films, 2011, 519, 3982-3985.	1.8	59
10	Characterisation of a low-pressure oxygen discharge created by surface waves. Journal Physics D: Applied Physics, 1989, 22, 1487-1496.	2.8	57
11	Growth and Modification of Organosilicon Films in PECVD and Remote Afterglow Reactors. Plasma Processes and Polymers, 2006, 3, 100-109.	3.0	57
12	Room temperature synthesis of carbon nanofibers containing nitrogen by plasma-enhanced chemical vapor deposition. Applied Physics Letters, 2004, 85, 1244-1246.	3.3	56
13	Polymer treatment in the flowing afterglow of an oxygen microwave discharge: Active species profile concentrations and kinetics of the functionalization. Plasma Chemistry and Plasma Processing, 1995, 15, 173-198.	2.4	55
14	XPS and NEXAFS characterisation of plasma deposited vertically aligned N-doped MWCNT. Diamond and Related Materials, 2005, 14, 891-895.	3.9	53
15	Silicon dioxide deposition in a microwave plasma reactor. Surface and Coatings Technology, 1999, 116-119, 868-873.	4.8	52
16	Influence of the excitation frequency on surface wave argon discharges: Study of the light emission. Journal of Applied Physics, 1987, 61, 1740-1746.	2.5	48
17	Modelling of low-pressure surface wave discharges in flowing oxygen: I. Electrical properties and species concentrations. Plasma Sources Science and Technology, 1998, 7, 524-536.	3.1	47
18	Optical spectroscopic analyses of OH incorporation into SiO[sub 2] films deposited from O[sub 2]/tetraethoxysilane plasmas. Journal of Vacuum Science and Technology A: Vacuum, Surfaces and Films, 2000, 18, 2452.	2.1	47

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19	Carbon nanowalls as material for electrochemical transducers. Applied Physics Letters, 2009, 95, .	3.3	47
20	Microstructure and composition of TiC/a-C:H nanocomposite thin films deposited by a hybrid IPVD/PECVD process. Surface and Coatings Technology, 2010, 204, 1880-1883.	4.8	35
21	Surface treatment of polypropylene by oxygen microwave discharge. Materials Science & Engineering A: Structural Materials: Properties, Microstructure and Processing, 1991, 139, 103-109.	5.6	34
22	In situ spectroscopic ellipsometry study of TiO2 films deposited by plasma enhanced chemical vapour deposition. Applied Surface Science, 2013, 283, 234-239.	6.1	34
23	Creating nanoporosity in silver nanocolumns by direct exposure to radio-frequency air plasma. Nanoscale, 2016, 8, 141-148.	5.6	34
24	Plasma depositionâ€"Impact of ions in plasma enhanced chemical vapor deposition, plasma enhanced atomic layer deposition, and applications to area selective deposition. Journal of Vacuum Science and Technology A: Vacuum, Surfaces and Films, 2020, 38, .	2.1	32
25	In situ ellipsometry and infrared analysis of PECVD SiO2 films deposited in an O2/TEOS helicon reactor. Journal of Non-Crystalline Solids, 1997, 216, 48-54.	3.1	31
26	Single chamber PVD/PECVD process for in situ control of the catalyst activity on carbon nanotubes growth. Surface and Coatings Technology, 2005, 200, 1101-1105.	4.8	30
27	Analysis of Low-k Organosilicon and Low-Density Silica Films Deposited in HMDSO Plasmas. Plasmas and Polymers, 2002, 7, 341-352.	1.5	29
28	Action of a static magnetic field on an argon discharge produced by a traveling wave. Journal of Applied Physics, 1989, 65, 1465-1478.	2.5	28
29	Limits of the PECVD process for single wall carbon nanotubes growth. Chemical Physics Letters, 2006, 421, 242-245.	2.6	28
30	Investigation of O-atom kinetics in O₂, CO₂, H₂O and O₂/HMDSO low pressure radiofrequency pulsed plasmas by time-resolved optical emission spectroscopy. Plasma Sources Science and Technology, 2007, 16, 597-605.	3.1	28
31	Study of oxygen/TEOS plasmas and thin SiOx films obtained in an helicon diffusion reactor. Surface and Coatings Technology, 1998, 98, 1578-1583.	4.8	27
32	Carbon nanotubes and nanostructures grown from diamond-like carbon and polyethylene. Applied Physics A: Materials Science and Processing, 2001, 73, 765-768.	2.3	27
33	Nanostructure and photocatalytic properties of TiO2 films deposited at low temperature by pulsed PECVD. Applied Surface Science, 2019, 466, 63-69.	6.1	27
34	Influence of plasma pulsing on the deposition kinetics and film structure in low pressure oxygen/hexamethyldisiloxane radiofrequency plasmas. Thin Solid Films, 2006, 514, 45-51.	1.8	26
35	Structure and properties of silicon oxide films deposited in a dual microwave-rf plasma reactor. Thin Solid Films, 2001, 384, 230-235.	1.8	25
36	Comparison of structure and mechanical properties of SiO2-like films deposited in O2/HMDSO pulsed and continuous plasmas. Surface and Coatings Technology, 2006, 200, 6517-6521.	4.8	25

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37	Impact of the etching gas on vertically oriented single wall and few walled carbon nanotubes by plasma enhanced chemical vapor deposition. Journal of Applied Physics, 2007, 101, 054317.	2.5	25
38	Synthesis of nickel-filled carbon nanotubes at 350 Â°C. Carbon, 2011, 49, 4595-4598.	10.3	25
39	Study of oxygen/tetraethoxysilane plasmas in a helicon reactor using optical emission spectroscopy and mass spectrometry. Plasma Sources Science and Technology, 2000, 9, 331-339.	3.1	24
40	Shape control of nickel nanostructures incorporated in amorphous carbon films: From globular nanoparticles toward aligned nanowires. Journal of Applied Physics, 2012, 111, .	2.5	24
41	Hierarchical carbon nanostructure design: ultra-long carbon nanofibers decorated with carbon nanotubes. Nanotechnology, 2011, 22, 435302.	2.6	23
42	Spectroscopic ellipsometry analysis of TiO2 films deposited by plasma enhanced chemical vapor deposition in oxygen/titanium tetraisopropoxide plasma. Thin Solid Films, 2012, 522, 366-371.	1.8	23
43	Unravelling local environments in mixed TiO2â€"SiO2 thin films by XPS and ab initio calculations. Applied Surface Science, 2020, 510, 145056.	6.1	23
44	In situ deposition and etching process of a-C:H:N films in a dual electron cyclotron resonanceâ€"radio frequency plasma. Diamond and Related Materials, 2000, 9, 573-576.	3.9	22
45	Electrical properties of low-dielectric-constant films prepared by PECVD in O2/CH4/HMDSO. Materials Science in Semiconductor Processing, 2002, 5, 279-284.	4.0	22
46	Growth, microstructure and electronic properties of amorphous carbon nitride films investigated by plasma diagnostics. Journal of Applied Physics, 1999, 86, 4668-4676.	2.5	21
47	Effect of ion bombardment on the structural and optical properties of TiO2 thin films deposited from oxygen/titanium tetraisopropoxide inductively coupled plasma. Thin Solid Films, 2015, 589, 783-791.	1.8	21
48	Experimental investigation of the respective roles of oxygen atoms and electrons in the deposition of SiO2 in O2/TEOS helicon plasmas. Journal of Vacuum Science and Technology A: Vacuum, Surfaces and Films, 1999, 17, 2470-2474.	2.1	20
49	Mechanisms Involved in the Conversion of ppHMDSO Films into SiO2-Like by Oxygen Plasma Treatment. Plasma Processes and Polymers, 2006, 3, 365-373.	3.0	20
50	Impact of the Cu-based substrates and catalyst deposition techniques on carbon nanotube growth at low temperature by PECVD. Microelectronic Engineering, 2007, 84, 2501-2505.	2.4	20
51	Early stages of the carbon nanotube growth by low pressure CVD and PE-CVD. Diamond and Related Materials, 2009, 18, 61-65.	3.9	20
52	TEM analysis of photocatalytic TiO2 thin films deposited on polymer substrates by low-temperature ICP-PECVD. Applied Surface Science, 2019, 491, 116-122.	6.1	20
53	Chemical etching of thin SiOxCyHz films by post-deposition exposure to oxygen plasma. Applied Surface Science, 1999, 138-139, 57-61.	6.1	19
54	Growth kinetics of low temperature single-wall and few walled carbon nanotubes grown by plasma enhanced chemical vapor deposition. Physica E: Low-Dimensional Systems and Nanostructures, 2007, 37, 34-39.	2.7	18

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55	Direct observation of water incorporation in PECVD SiO2 films by UV-Visible ellipsometry. Thin Solid Films, 1997, 311, 212-217.	1.8	17
56	Preparation and modification of carbon nanotubes electrodes by cold plasmas processes toward the preparation of amperometric biosensors. Electrochimica Acta, 2010, 55, 7916-7922.	5.2	17
57	Structural and Optical Properties of PECVD TiO₂-SiO₂Mixed Oxide Films for Optical Applications. Plasma Processes and Polymers, 2016, 13, 918-928.	3.0	17
58	Effect of growth interruptions on TiO 2 films deposited by plasma enhanced chemical vapour deposition. Materials Chemistry and Physics, 2016, 182, 409-417.	4.0	15
59	Microwave plasma in argon produced by a surface wave: study of the effect of pressure on the optical emission and the potentials for analysis of gaseous samples. Spectrochimica Acta, Part B: Atomic Spectroscopy, 1988, 43, 963-970.	2.9	14
60	Analysis of Tiâ€“Siâ€“N diffusion barrier films obtained by r.f. magnetron sputtering. Microelectronic Engineering, 2000, 50, 509-513.	2.4	14
61	Ionized Physical Vapour Deposition combined with PECVD, for synthesis of carbonâ€“metal nanocomposite thin films. Solid State Sciences, 2009, 11, 1824-1827.	3.2	14
62	Comparative Study of Films Deposited from HMDSO/O2 in Continuous Wave and Pulsed rf Discharges. Plasma Processes and Polymers, 2007, 4, S287-S293.	3.0	13
63	Titanium carbide/carbon composite nanofibers prepared by a plasma process. Nanotechnology, 2010, 21, 435603.	2.6	13
64	Titanium carbide/carbon nanocomposite hard coatings: A comparative study between various chemical analysis tools. Surface and Coatings Technology, 2014, 256, 41-46.	4.8	12
65	TiO₂â€“SiO₂ nanocomposite thin films deposited by direct liquid injection of colloidal solution in an O₂/HMDSO low-pressure plasma. Journal Physics D: Applied Physics, 2021, 54, 085206.	2.8	12
66	Structural and optical properties of RF-biased PECVD TiO2 thin films deposited in an O2/TTIP helicon reactor. Vacuum, 2016, 131, 231-239.	3.5	11
67	Experimental study of Tiâ€“Siâ€“N films obtained by radio frequency magnetron sputtering. Surface and Coatings Technology, 1999, 116-119, 922-926.	4.8	10
68	Fabrication of a nickel nanowire mesh electrode suspended on polymer substrate. Nanotechnology, 2012, 23, 275603.	2.6	10
69	Measurements of rf bias effect in a dual electron cyclotron resonance-rf methane plasma using the Langmuir probe method. Journal of Vacuum Science and Technology A: Vacuum, Surfaces and Films, 2000, 18, 497-502.	2.1	9
70	Characterization of carbon nanotubes and carbon nitride nanofibres synthesized by PECVD. EPJ Applied Physics, 2006, 34, 157-163.	0.7	9
71	Modification of the optical properties and nano-crystallinity of anatase TiO2nanoparticles thin film using low pressure O2 plasma treatment. Thin Solid Films, 2020, 709, 138212.	1.8	9
72	Argon surface wave discharges at medium pressure. Experiments and discussion on the energy balance. Revue De Physique AppliquÃ©e, 1987, 22, 999-1006.	0.4	9

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73	First developments for photonics integrated on plasma-polymer-HMDSO: Single-mode TE00â€“TM00 straight waveguides. Optical Materials, 2007, 30, 657-661.	3.6	8
74	Integration of a carbon nanotube based electrode in silicon microtechnology to fabricate electrochemical transducers. Nanotechnology, 2008, 19, 435502.	2.6	8
75	Influence of Ion Bombardment and Annealing on the Structural and Optical Properties of TiO_{<i>x</i>} Thin Films Deposited in Inductively Coupled TTIP/O₂ Plasma. Plasma Processes and Polymers, 2009, 6, S741.	3.0	8
76	Highly ordered ultralong magnetic nanowires wrapped in stacked graphene layers. Beilstein Journal of Nanotechnology, 2012, 3, 846-851.	2.8	8
77	Microstructure and Photocatalytic Properties of TiO2â€“Reduced Graphene Oxide Nanocomposites Prepared by Solvothermal Method. Journal of Electronic Materials, 2018, 47, 7372-7379.	2.2	8
78	Low-Pressure Argon Discharge Sustained by a Wave with an External Applied Magnetic Field. Europhysics Letters, 1988, 6, 413-418.	2.0	7
79	The combined study of the organosilicon films by RBS, ERDA and AFM analytical methods obtained from PECVD and PACVD. Surface Science, 2004, 566-568, 1143-1146.	1.9	7
80	Structural characterization and electrochemical behavior of titanium carbon thin films. Surface and Coatings Technology, 2012, 211, 192-195.	4.8	7
81	The influence of Ni content on the characteristics of Câ€“Ni thin films. Surface and Coatings Technology, 2012, 211, 188-191.	4.8	7
82	Production of argon metastable atoms in high pressure (20-300 Torr) microwave discharges. Revue De Physique AppliquÃ©e, 1988, 23, 1749-1754.	0.4	7
83	Estimation of the TEOS dissociation coefficient by electron impact. Journal of Vacuum Science and Technology A: Vacuum, Surfaces and Films, 2000, 18, 2728-2732.	2.1	6
84	Low temperature plasma carbon nanotubes growth on patterned catalyst. Microelectronic Engineering, 2006, 83, 2427-2431.	2.4	6
85	H atom surface loss kinetics in pulsed inductively coupled plasmas. Plasma Sources Science and Technology, 2013, 22, 055004.	3.1	6
86	Tailoring the chemistry and the nano-architecture of organic thin films using cold plasma processes. Plasma Processes and Polymers, 2017, 14, 1700042.	3.0	6
87	Hybrid approaches coupling solâ€“gel and plasma for the deposition of oxide-based nanocomposite thin films: a review. SN Applied Sciences, 2021, 3, 1.	2.9	6
88	Surface Wave Plasmas in O2-N2 Mixtures as Active Species Sources for Surface Treatments. NATO ASI Series Series B: Physics, 1993, , 491-501.	0.2	6
89	Mass spectrometric investigation of the positive ions formed in low-pressure oxygen/tetraethoxysilane and argon/tetraethoxysilane plasmas. Journal of Applied Physics, 2001, 89, 5227-5229.	2.5	5
90	Single- and Few-Walled Carbon Nanotubes Grown at Temperatures as Low as 450 Â°C: Electrical and Field Emission Characterization. Journal of Nanoscience and Nanotechnology, 2007, 7, 3350-3353.	0.9	4

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91	Influence of ion bombardment on structural and electrical properties of SiO2thin films deposited from O2/HMDSO inductively coupled plasmas under continuous wave and pulsed modes. EPJ Applied Physics, 2008, 42, 3-8.	0.7	4
92	Unveiling a critical thickness in photocatalytic TiO₂ thin films grown by plasma-enhanced chemical vapor deposition using real time in situ spectroscopic ellipsometry. Journal Physics D: Applied Physics, 2021, 54, 445303.	2.8	4
93	Growth mechanisms of carbon nanotubes converted from diamond-like carbon films. Chemical Physics Letters, 2004, 397, 516-519.	2.6	3
94	ERDA and Structural Characterization of Oriented Multiwalled Carbon Nanotubes. Journal of Physical Chemistry C, 2007, 111, 10353-10358.	3.1	3
95	Annealing and biasing effects on the structural and optical properties of PECVD-grown TiO2 films from TTIP/O2 plasma. Journal of Materials Science: Materials in Electronics, 2018, 29, 13254-13264.	2.2	3
96	Ion impingement effect on the structure and optical properties of Ti x Si 1âˆ’ x O 2 films deposited by ICPâ€PECVD. Plasma Processes and Polymers, 2019, 16, 1900034.	3.0	3
97	Anatase TiO2 deposited at low temperature by pulsing an electron cyclotron wave resonance plasma source. Scientific Reports, 2020, 10, 21952.	3.3	3
98	Low-temperature deposition of self-cleaning anatase TiO2 coatings on polymer glazing via sequential continuous and pulsed PECVD. Surface and Coatings Technology, 2022, 436, 128256.	4.8	3
99	Response to â€œComment on â€˜Carbon nanowalls as material for electrochemical tranducersâ€™ â€•[Appl. Phys. Lett. 96 126102 (2010)]. Applied Physics Letters, 2010, 96, 126103.	3.3	2
100	The Effect of Plasma Gas Composition on the Nanostructures and Optical Properties of TiO2 Films Prepared by Helicon-PECVD. Nano, 2018, 13, 1850124.	1.0	1
101	Versatile SOG/SU-8/fluorinated SU-8 rib optical waveguides as microsystems: single-mode TE 00 -TM 00 straight waveguides, S-Bends, Y-Junctions, Mach-Zehnder interferometers. , 2005, 5956, 233.		0
102	Study of magnetic field influence on charged species in a low pressure helicon reactor. European Physical Journal D, 2006, 56, B1091-B1096.	0.4	0
103	Photonics integrated circuits on plasma-polymer-HMDSO: Single-mode TE00-TM00 straight waveguides, S-Bends, Y-Junctions and Mach-Zehnder Interferometers. , 2006, , .		0
104	Integrated optics based on plasma processed dielectric materials. Proceedings of SPIE, 2008, , .	0.8	0
105	X-ray reflectometry study of diamond-like carbon films prepared by plasma enhanced chemical vapor deposition in a low pressure inductively coupled plasma. Thin Solid Films, 2013, 537, 102-107.	1.8	0